

Amendments to the Specification

Please replace paragraph [0035] with the following amended paragraph:

[0035] Generally, whether a gas or ionized gas will be considered to be an antistatic agent can be determined empirically in a number of different ways. According to one approach, one or more wafers are processed in a MERCURY® tool according to a process recipe comprising at least one rinse step and at least one dry step. In a first run, the gas under consideration is not introduced into the process chamber in any rinse or drying step. Charge buildup, C1, on the wafer(s) at the end of the recipe is then measured and an average is determined. Meanwhile, in a second run, the same process is carried out except that the gas under consideration is introduced into the process chamber during the entirety of all rinse and dry steps. To carry out the test, the candidate gas is introduced into the chamber in admixture with N2 carrier gas at a concentration such that the weight ratio of the carrier gas to candidate gas is about 60:1. Charge build up, C2, on the wafer(s) at the end of the recipe is then measured and an average is determined. The candidate gas will be deemed to be an antistatic agent if the ratio given by $\frac{C2}{C1}$ (average values) is less than about 0.25, more preferably less than about 0.1, and more preferably less than about 0.01. More preferably, a gas will be deemed to be an antistatic agent if the average value of C2 is less than about -1.0 kV, more preferably less than about -0.1 kV.